

(12) INTERNATIONAL APPLICATION PUBLISHED UNDER THE PATENT COOPERATION TREATY (PCT)

(19) World Intellectual Property
Organization
International Bureau



(43) International Publication Date
14 April 2005 (14.04.2005)

PCT

(10) International Publication Number
WO 2005/034261 A1

(51) International Patent Classification⁷: **H01L 51/30**

(74) Agents: ASAHI, Kazuo et al.; Nishi-Shinbashi Noa Bldg., 4th Floor, 18-9, Nishi-Shinbashi 1-chome, Minato-ku, Tokyo 105-0003 (JP).

(21) International Application Number:

PCT/JP2004/014458

(81) Designated States (unless otherwise indicated, for every kind of national protection available): AE, AG, AL, AM,

(22) International Filing Date:

24 September 2004 (24.09.2004)

AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NA, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW.

(30) Priority Data:

2003-343703 1 October 2003 (01.10.2003) JP

(84) Designated States (unless otherwise indicated, for every kind of regional protection available): ARIPO (BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW), Eurasian (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM), European (AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IT, LU, MC, NL, PL, PT, RO, SE, SI, SK, TR), OAPI (BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG).

(71) Applicant (for all designated States except US): **SEIKO EPSON CORPORATION [JP/JP]; 4-1, Nishishinjuku 2-chome, Shinjuku-ku, Tokyo 163-0811 (JP).**

Published:

— with international search report

For two-letter codes and other abbreviations, refer to the "Guidance Notes on Codes and Abbreviations" appearing at the beginning of each regular issue of the PCT Gazette.

(72) Inventors; and

(75) Inventors/Applicants (for US only): **SHINOHARA, Takashi [JP/JP]; c/o Seiko Epson Corporation, 3-5, Owa 3-chome, Suwa-shi, Nagano-ken 392-8502 (JP). SHINOHARA, Yuji [JP/JP]; c/o Seiko Epson Corporation, 3-5, Owa 3-chome, Suwa-shi, Nagano-ken 392-8502 (JP). TERAO, Koichi [JP/JP]; c/o Seiko Epson Corporation, 3-5, Owa 3-chome, Suwa-shi, Nagano-ken 392-8502 (JP).**

WO 2005/034261 A1

(54) Title: METHOD FOR PRESERVING ORGANIC POLYMERIC MATERIAL AND ORGANIC ELECTROLUMINESCENT DEVICE

(57) Abstract: A method for preserving an organic polymeric material, wherein an organic polymeric material which exhibits strong acidity is preserved with it being dissolved or dispersed in a liquid mainly comprised of water, the method is characterized in that the organic polymeric material is preserved with it being dissolved or dispersed in the liquid so that a concentration thereof is 2 wt%, and a pH (at 25°C) of the thus obtained liquid is measured and then adjusted so as to be higher than the measured pH (at 25°C). Further, it is preferred that a pH (25°C) of the liquid before the pH adjustment is 2.2 or lower and a pH (25°C) of the liquid after the pH adjustment is in the range of 2.5 to 7.5. According to this, even if the organic polymeric material is preserved for a long period of time, it is possible to prevent or reduce a change in a molecular structure thereof with the lapse of time.